

L Number	Hits	Search Text	DB	Time stamp
1	1	6028394.pn.	USPAT; EPO; JPO; IBM_TDB	2003/05/21 09:00
2	2	(isopropyl or ethanol or methanol or alcohol) same bubbl\$3 same (HF or hydrofluoric) same ("silicon oxide" or "SiO.sub.2")	USPAT; EPO; JPO; IBM_TDB	2003/05/21 09:05
3	2258	(isopropyl or ethanol or methanol or alcohol) and vapor\$3 and (HF or hydrofluoric) and ("silicon oxide" or "SiO.sub.2")	USPAT; EPO; JPO; IBM_TDB	2003/05/21 11:01
4	27	(isopropyl or ethanol or methanol or alcohol) same vapor\$3 same (HF or hydrofluoric) same ("silicon oxide" or "SiO.sub.2")	USPAT; EPO; JPO; IBM_TDB	2003/05/21 09:07
6	1	5439553.pn.	USPAT; EPO; JPO; IBM_TDB	2003/05/21 10:11
9	38652	MEMS or "micro electro mechanical system" or microstructure	USPAT; EPO; JPO; IBM_TDB	2003/05/21 10:57
10	6050	(MEMS or "micro electro mechanical system" or microstructure) and ("silicon oxide" or "SiO.sub.2" or pSG or BPSG or TEOS or sacrificial)	USPAT; EPO; JPO; IBM_TDB	2003/05/21 10:59
11	230	((MEMS or "micro electro mechanical system" or microstructure) and ("silicon oxide" or "SiO.sub.2" or pSG or BPSG or TEOS or sacrificial)) and ((isopropyl or ethanol or methanol or alcohol) and vapor\$3 and (HF or hydrofluoric) and ("silicon oxide" or "SiO.sub.2"))	USPAT; EPO; JPO; IBM_TDB	2003/05/21 11:00
12	2123	(isopropyl or ethanol or methanol or alcohol) and vapor\$3 and (HF or hydrofluoric) and ("silicon oxide" or "SiO.sub.2") and (etch\$3 or remov\$3)	USPAT; EPO; JPO; IBM_TDB	2003/05/21 11:03
13	569	((isopropyl or ethanol or methanol or alcohol) and vapor\$3 and (HF or hydrofluoric) and ("silicon oxide" or "SiO.sub.2") and (etch\$3 or remov\$3)) and 438/\$.ccls.	USPAT; EPO; JPO; IBM_TDB	2003/05/21 11:03
14	175	("silicon oxide" or "SiO.sub.2") same (remov\$3 or etch\$3) same (microstructure or MEMS)	USPAT; EPO; JPO; IBM_TDB	2003/05/21 11:04